## **SEMATECH 7th Annual Mask Cleaning Workshop 2010**

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Part 1		1
KEYNOTE: EUV Mask Cleaning: Progress and Issue	Naoya Hayashi, DNP	7
Investigation of Ozonated Water for Ruthenium-Capped EUV Mask Cleaning	Seungho Lee, Hanyang University	52
The Power of Light- A Leap in Performance	Uwe Dietze, Suss (Hamatech)	60
Qualification of BitClean Technology in Photomask Production	Ron Bozak, RAVE N.P.Inc	90
EUV Mask and Blank Cleaning Requirement for 16nm HP node	Abbas Rastegar, SEMATECH	113
Part 2		124
CO <sub>2</sub> Cryogenic Aerosol Technology Development for EUV Mask Cleaning & Restoration	Ivin Varghese, Eco-snow Systems, RAVE N.P. Inc	126
Acoustic Characterization of an Ultrasonic or Megasonic Cleaning System	Petrie Yam, ONDACorporation	142
KEYNOTE: EUV Actinic Inspection and Broad Review of Current EUV Mask Status	Kenneth Goldberg, Lawrence Berkeley National Laboratory	161
Lasertec EUV Tool Development Status	Ji Lee, Lasertec Corp.	204
Novel Method for EUV Blank Phase Defect Control Using Ultrashort Laser Technology-Concept & Feasibility	Guy Ben-Zvi, Carl Zeiss	212
Part 3		227
Effect of GaN Thin Film Thickness on Particle Adhesion in Semiconductor Applications	Katie Smith, Purdue University	229
Time Dependent Defects and Atmospheric Storage of EUV masks	Oleg Kishkovich, Entegris	240
Influence of Mask Surface Roughness on EUV	Eun-jin Kim,	251

Hanyang University Wolfgang Harnisch,

Carl Zeiss

Overview on Carl Zeiss EUV Mask Tools Roadmap